

Manufacturer
 HARRICK

Model
 PCD-002-CE



Plasma Cleaner



Plasma creation for surface preparation

The equipment generates an O₂ plasma at low pressures and high frequency voltages for surface modification.

It allows processes as:

- Removal of organic contamination from surfaces
- Modification/enhancement of physical and/or chemical characteristics of surfaces, required in further processes
- Plasma bonding: PDMS/glass, PDMS/PDMS

Technical specifications

- Chamber dimensions: 6 inches in diameter x 6.5 inches in depth
- Plasma available: Oxygen and air
- Pressure range: from 200 mtorr to 1500 mtorr
- Flow rate: 5 SCFH to 10 SCFH
- Radio frequency: from 8 MHz to 12 MHz
- Power: 7.2W (Low), 10.2W (Medium), 29.6W (High)
- PlasmaFlo air flow mixer with two gas inlets
- Maximal flowrate: 65 mL/min ± 1.3 mL/min